

10/660,914

Chao-Peng Chen et al.

09/12/03

Group Art Unit

(Use several shouts if necessary)

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Ch 4

5/2006

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HTIRC-02-013

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<div style="display: flex; align-items: center;"> <div style="border: 1px solid black; padding: 5px; margin-right: 10px;">             Cuy-           </div> <div style="border: 1px solid black; padding: 5px;">             Chemistry of a Chemically Amplified Negative Resist and Process Modification for Electron Beam Exposure, by Shigeki Yamamoto et al., Presented by Patrick Martens, Sumitomo Chemical America.           </div> </div>
<div style="display: flex; align-items: center;"> <div style="border: 1px solid black; padding: 5px; margin-right: 10px;">             Cuy-           </div> <div style="border: 1px solid black; padding: 5px;">             Perpendicular Recording Head Technology, DASCAM Business Group, TDK Corp., Japan, 07/23/02, p.5.           </div> </div>

**EXAMINER**

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Cury	"Bake Condition Effect on Hybrid Lithography Process for Negative Tone Chemically Amplified Resists", by L. Pain et al
	Advances in Resist Technology and Processing XVII,
	Francis M. Houlihan, Editor, Proc. of SPIE, Vol. 3999
	(2000), 0277-786X/00.

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